



IVS TECHNICAL WORKSHOP

ATOMIC LAYER DEPOSITION

Thursday, July 8, 2010
Bar-Ilan University, Ramat Gan

8:00-08:50	Registration
8:50-09:00	Greetings
	Short Course, Steven George Univ. of Colorado, Boulder:
9:00-11:00	Short Course Session I
11:00-11:25	Coffee Break
11:25-13:15	Short Course Session II
13:15-14:10	Lunch
	Technical Session
14:10-14:50	Eric W. Deguns, Cambridge NanoTech: "ALD Applications for Research and Development: from High Aspect Ratio Features to Plasma Enhanced Deposition"
14:50-15:30	Ville Malinen, Beneq: "ALD from R&D to Industry: Selected Examples Beyond IC Technology"
15:30-16:10	Juhana Kostamo, Picosun: " Bridging Between Research and Production with ALD Technology: Selected Design Considerations"
16:10-16:40	Coffee Break
	Research Talks
16:40-17:15	Joseph Salzman, Technion "High-k Dielectric Layers for Low Power Microelectronics and Nonvolatile Memory Devices"
17:15-17:50	Fernando Patolsky, Tel Aviv University "Heteroepitaxial Si/ZnO Hierarchical Nanostructures for Future Optoelectronic Devices"
	Tours of Bar Ilan Nanocenter/ALD Facilities (sign-up during workshop):
18:00-18:30	Tour # I
18:30-19:00	Tour # II